stable of the group discussed here, correspond to the least stabilized o-quinodimethanes of the series.¹²

From the synthetic point of view, the sulfone photolysis reaction has practical utility. Thus, the conversion of the diphenyl sulfones III and IX to the corresponding condensed cyclobutenes VI and X can be accomplished only photochemically. The effective pyrolysis temperatures of sulfones III and IX are higher than the temperature at which the cyclobutenoid hydrocarbons VI and X rearrange to secondary pyrolysis products.^{8,13}



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(12) The possibility that sulfones I, II, III, and IX all decompose initially by homolyt'c fission to diradicals appears unlikely on the basis of the marked difference in the photolytic stabilities of II and III. Whereas the *o*-quinoid hydrocarbons generated from II and III (i and ii) by concerted loss of sulfur dioxide are structures of very different energy content, the diradicals (iii and iv) formed from II and III by rupture of a carbon-sulfur bond are structures which should have very similar energy.



(13) Sulfone III is stable at $150^\circ,$ at which temperature hydrocarbon VI rearranges to a phenyldihydronaphthacene 5b

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Bond Dissociation Energies and Ion Energetics in Organosilicon Compounds by Electron Impact

Sir:

Recent reports^{1,2} of electron impact studies of silane. disilane, and alkyl-substituted silanes have indicated that silicon-silicon and silicon-hydrogen bonds are considerably stronger than thermochemical data would suggest, and that silicon-carbon bonds are of comparable strength to the analogous carbon-carbon bonds. In electron impact studies of the formation of the trimethylsiliconium ion from substituted trimethylsilanes we have obtained results of a similar nature. The compounds studied were synthesized in this laboratory by standard methods³ from trimethylchlorosilane and hexachlorodisilane. Appearance potentials of the $(CH_3)_3Si^+$ ion were determined by the retarding-potential-difference method⁴ on a modified Bendix Model 14-101 time-of-flight mass spectrometer. The energy spread of the electrons was approximately 0.1 e.v.; xenon was used to calibrate the electron energy scale. Results are shown in Table I, where the indicated errors are average deviations of replicate measurements.

TABLE I

(CH₁)₁Si⁺ Appearance Potentials and Bond Dissociation Energies in Substituted Trimethylsilanes

Bond	A [(CH₃)₃Si ⁺], e.v.	ΔH_{f}° [(CH ₃) ₃ - Si ⁺], kcal. mole ⁻¹	ΔH_{f}° [(CH ₃) ₃ - Si-X], kcal. mole ⁻¹	D [(CH3)3 Si-X], kcal. mole ⁻¹
(CH ₃) ₃ Si-H	10.78 ± 0.07	137	- 60°	83
(CH ₃) ₃ Si-CH ₃	10.63 ± 0.13	143	-69^{a}	79
$(CH_3)_3Si-C_2H_5$	10.53 ± 0.09		- 77	77
$(CH_3)_3Si-CH(CH_3)_2$	10.56 ± 0.16		- 91	77
$(CH_3)_3Si-C(CH_3)_3$	10.53 ± 0.09		- 98	77
(CH ₂) ₂ Si-Cl	12.42 ± 0.03		-118	120
(CH ₃) ₃ Si-Si(CH ₃) ₃	10.69 ± 0.04		-129^{b}	81

 a Reference 7. b Estimated by group equivalent method of Franklin. 10

Our appearance potential of $(CH_3)_3Si^+$ from trimethylsilane agrees well with that of Hobrock and Kiser.⁵ On the other hand, the value of $A[(CH_3)_3Si^+]$ from tetramethylsilane is in serious disagreement with that determined by Hobrock and Kiser,⁶ ours being lower by nearly 0.7 e.v. We believe our value is to be preferred, because taking simple dissociation processes, *viz*.

 $(\mathbf{CH}_3)_3\mathbf{SiH} + \mathbf{e} \longrightarrow (\mathbf{CH}_3)_2\mathbf{Si}^- + \mathbf{H} + 2\mathbf{e} \qquad (1)$

$$(CH_2)_3SiCH_2 + e \longrightarrow (CH_2)_3Si^+ + CH_2 + 2e$$
 (2)

assuming no excess energy involved, and combining with thermochemical data^{7,8} leads to consistent values for $\Delta H_{\rm f}^{\circ}[(CH_3)_3Si^+]$ (column 3, Table I). Assuming that $(CH_3)_3Si^+$ is formed from all compounds by simple

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processes analogous to eq. 1 and 2 and combining the appearance potentials with the implied value of 140 ± 3 kcal. mole⁻¹ for $\Delta H_f^{\circ}[(CH_3)_3Si^+]$ and with thermochemical values for the radical heats of formation^{8,9} leads to molecular heats of formation for $(CH_3)_3SiC_2H_5$, $(CH_3)_3SiCH(CH_3)_2$, $(CH_3)_3SiC(CH_3)_3$, and $(CH_3)_3SiCl$ (column 4, Table I). To our knowledge there are no reported values for $\Delta H_f^{\circ}[(CH_3)_6Si_2]$ and, of course, it cannot be obtained from the electron impact data since $\Delta H_f^{\circ}[(CH_3)_3Si]$ is unknown.

We have estimated $\Delta H_{f}^{\circ}[(CH_{3})_{6}Si_{2}]$ as -129 kcal. mole⁻¹ by means of the group equivalent method of Franklin¹⁰ using the heats of formation shown in column 4, Table I. We may use the same heats of formation to deduce the bond energy parameters required by Allen's calculational method.^{11,12} These parameters, which are consistent with those for other substituted paraffins,¹² yield a value for $\Delta H_{\rm f}^{\circ}[(\rm CH_3)_6\rm Si_2]$ that is within a few kilocalories per mole of that obtained by Franklin's method. Combination of our estimate of $\Delta {\cal H}_{f}{}^{o}\left[(CH_{3})_{6}\mathrm{Si}_{2}\right]$ with the appearance potential of $(CH_3)_3Si^+$ from $(CH_3)_6Si_2$ and with $\Delta H_f^{\circ}[(CH_3)_3Si^+]$ gives 7.2 e.v. for the ionization potential of the $(CH_3)_3Si$ radical or, equivalently, a value of -22 kcal. mole⁻¹ for $\Delta H_{\rm f}^{\circ}[(CH_3)_3Si]$. This is expressed as bond dissociation energy of $(CH_3)_3Si-X$ in column 5 of Table I. The uncertainty in these dissociation energies which is estimated as ± 10 kcal./mole arises principally from the estimate of $\Delta H_{f}^{\circ}[(CH_{3})_{6}Si_{2}].$

Some indirect support for the ionization potential of the $(CH_3)_3Si$ radical (and therefore for the bond dissociation energies) may be derived from the following consideration: the appearance potential of m/e = 57from $(CH_3)_3SiC(CH_3)_3$, namely 11.88 e.v., is too high to reflect a simple dissociation process to $(CH_3)_3C^+$ and $(CH_3)_3Si$. If Stevenson's rule¹³ can be applied to organosilanes as well as to paraffinic hydrocarbons, one derives the following relationship of radical ionization potentials

 $I_{z}[(CH_{3})_{3}Si] < I_{z}[(CH_{3})_{3}C] = 7.42^{14}$

Hence, lower limits for $D[(CH_3)_3Si-X]$ that are only 5 kcal. mole⁻¹ less than those in Table I are quite certain.

As found by previous investigators^{1,2} the Si–H and Si–Si bonds (particularly the latter) are considerably stronger than indicated by the thermochemical bond energies of 77.4 and 47.9 kcal. mole⁻¹, respectively.¹² Also, the dissociation energies of the C–Si bonds are of comparable magnitude to the corresponding C–C bonds although the dependence on alkyl type (R) is much less than for H₃Si–R bonds² or R–R bonds.¹⁵

The data in Table I indicate that in the gas phase the trimethylsiliconium ion is sometimes somewhat easier to form from its molecular precursor than is the corresponding *t*-butylcarbonium ion. This is perhaps better seen in Table II in which we compare the difference between the heats of formation of the ions¹⁶ and

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Interestingly enough only in the case of the chloride is there any really significant difference in the ease of formation of the trimethylsiliconium and trimethylcarbonium ions, and in this case the large difference reflects the large dissociation energy of the Si-Cl bond.

In connection with possible significance of the data in Table II for reactions in solution, it is interesting to note the previous conclusion, based on various lines of

Table II

Comparison of Siliconium and Carbonium Ionic Stabilities

Compound	ΔH_{f}° $[(CH_{3})_{3}Si^{+}] - \Delta H_{f}^{\circ}[(CH_{3})_{3}-Si^{-}X], kcal.$ $mole^{-1}$	Compound	ΔH_{f}° $[(CH_{i})_{i}C^{+}] - \Delta H_{f}^{\circ}[(CH_{i})_{i}- C^{-}X], kcal.$ mole ⁻¹
CH₃)₃SiH	2 00	(CH ₂) ₃ CH	208
CH ₃) ₃ SiCH ₃	2 0 9	(CH ₃) ₃ CCH ₃	217
CH ₃) ₃ SiC ₂ H ₅	217	$(CH_3)_3CC_2H_5$	222
CH ₃) ₃ SiCH(CH ₃) ₂	231	$(CH_3)_3CCH(CH_3)_2$	226
CH ₃) ₃ SiC(CH ₃) ₃	238	$(CH_3)_3CC(CH_3)_3$	236
CH ₃) ₃ SiCl	258	(CH ₃) ₃ CCl	209

evidence, that reaction 3 proceeds via the siliconium ion-pair intermediate¹⁷, and the previously expressed conviction¹⁷ that trialkylsilicon cations, R_3Si^+ , and trialkylcarbon cations, R_3C^+ may, in certain circumstances, be of comparable stability relative to their precursors.

 $(CH_3)_3SiCH_2CH_2Cl + C_2H_5OH \cdot H_2O \longrightarrow (CH_3)_8SiOR + C_2H_4 + HCl (R = H \text{ or } C_2H_5)$ (3)

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Pulse Radiolytic Determination of pK for Hydroxyl Ionic Dissociation in Water¹

Sir:

In several papers² the dissociation of OH has been assumed to account for radiation chemical results in alkaline solutions. The reaction most likely is

$$OH + OH^{-} \xrightarrow{} H_{2}O + O^{-}$$
(1)

However, previous data did not permit calculation of the dissociation constant for OH, and values deduced

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